

UNITED STATES PATENT AND TRADEMARK OFFICE

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BEFORE THE PATENT TRIAL AND APPEAL BOARD

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TAIWAN SEMICONDUCTOR MANUFACTURING COMPANY, LTD.  
and TSMC NORTH AMERICA CORP.,  
Petitioners,

v.

ZOND, LLC,  
Patent Owner.

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Case IPR2014-00827  
Patent 6,853,142 B2

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Before KEVIN F. TURNER, DEBRA K. STEPHENS, JONI Y. CHANG,  
SUSAN L. C. MITCHELL, and JENNIFER M. MEYER,  
*Administrative Patent Judges.*

TURNER, *Administrative Patent Judge.*

DECISION  
Institution of *Inter Partes* Review  
37 C.F.R. § 42.108

## I. INTRODUCTION

Taiwan Semiconductor Manufacturing Company, Ltd. and TSMC North America Corporation (collectively “TSMC”) filed a Petition requesting *inter partes* review of claims 22, 23, 25, 29, 30, 33–36, 39, and 43 of U.S. Patent No. 6,853,142 B2 (“the ’142 Patent”). Paper 1 (“Pet.”). Zond, LLC (“Zond”) filed a Preliminary Response. Paper 8 (“Prelim. Resp.”). We have jurisdiction under 35 U.S.C. § 314, which provides that an *inter partes* review may not be instituted “unless . . . there is a reasonable likelihood that the petitioner would prevail with respect to at least 1 of the claims challenged in the petition.”

Upon consideration of TSMC’s Petition and Zond’s Preliminary Response, we conclude that the information presented in the Petition demonstrates that there is a reasonable likelihood that TSMC would prevail in challenging claims 22, 23, 25, 29, 30, 33–36, 39, and 43 as unpatentable under 35 U.S.C. § 103(a). Pursuant to 35 U.S.C. § 314, we hereby authorize an *inter partes* review to be instituted as to claims 22, 23, 25, 29, 30, 33–36, 39, and 43 of the ’142 Patent.

### A. *Related Matters*

TSMC indicates that the ’142 Patent was asserted in *Zond, LLC v. Fujitsu*, No.1:13-cv-11634-WGY (D. Mass.), in which TSMC is a co-defendant. Pet. 1. TSMC also identifies other matters where Zond asserted the claims of the ’142 Patent against third parties, as well as other Petitions for *inter partes* review that are related to this proceeding. *Id.*

*B. The '142 Patent*

The '142 Patent relates to methods and apparatus for generating high-density plasma. Ex. 1301, Abs. At the time of the invention, sputtering was a well-known technique for depositing films on semiconductor substrates. *Id.* at 1:16–24. The '142 Patent indicates that prior art magnetron sputtering systems deposit films having low uniformity and poor target utilization (the target material erodes in a non-uniform manner). *Id.* at 3:32–36. To address these problems, the '142 Patent discloses that increasing the power applied between the target and anode can increase the uniformity and density in the plasma. *Id.* at 3:37–44. However, increasing the power also “can increase the probability of generating an electrical breakdown condition leading to an undesirable electrical discharge (an electrical arc) in the chamber 104.” *Id.*

According to the '142 Patent, forming a weakly-ionized plasma substantially eliminates the probability of establishing a breakdown condition in the chamber when high-power pulses are applied between the cathode and anode. *Id.* at 6:21–30. Once the weakly-ionized plasma is formed, high-power pulses are applied between the cathode and anode to generate a strongly-ionized plasma from the weakly-ionized plasma. *Id.* at 7:23–36. The '142 Patent also discloses that the provision of the feed gas to the plasma allows for homogeneous diffusion of the feed gas in the weakly-ionized plasma and allows for the creation of a highly uniform strongly-ionized plasma. *Id.* at 6:31–35.

*C. Illustrative Claims*

Of the challenged claims, all are dependent and all depend from one of claims 21 or 31. Claims 21 and 22, reproduced below, are illustrative:

21. An apparatus for generating a strongly-ionized plasma, the apparatus comprising:

an anode;

a cathode that is positioned adjacent to the anode and forming a gap there between;

an ionization source that generates a weakly-ionized plasma proximate to the cathode, the weakly-ionized plasma reducing the probability of developing an electrical breakdown condition between the anode and the cathode; and

a power supply that produces an electric field across the gap, the electric field generating excited atoms in the weakly-ionized plasma and generating secondary electrons from the cathode, the secondary electrons ionizing the excited atoms, thereby creating the strongly-ionized plasma.

22. The apparatus of claim 21 wherein the power supply generates a constant power.

Ex. 1301, 21:61–22:11.

*D. Prior Art Relied Upon*

TSMC relies upon the following prior art references:

Wang                                      US 6,413,382 B1    July 2, 2002                      (Ex. 1305)

D.V. Mozgrin, et al., *High-Current Low-Pressure Quasi-Stationary Discharge in a Magnetic Field: Experimental Research*, 21 PLASMA PHYSICS REPORTS 400–409 (1995) (Ex. 1303) (hereinafter “Mozgrin”).

A. A. Kudryavtsev and V.N. Skerbov, *Ionization Relaxation in a Plasma Produced by a Pulsed Inert-Gas Discharge*, 28 SOV. PHYS. TECH. PHYS. 30–35 (Jan. 1983) (Ex. 1304) (hereinafter “Kudryavtsev”).

*E. Asserted Grounds of Unpatentability*

TSMC asserts the following grounds of unpatentability:

Claim(s)	Basis	References
22, 23, 25, 29, 30, 33–36, 39, and 43	§ 103(a)	Mozgrin and Kudryavtsev
22, 23, 25, 29, 30, 33–36, 39, and 43	§ 103(a)	Wang and Kudryavtsev

II. ANALYSIS

*A. Claim Construction*

In an *inter partes* review, claim terms in an unexpired patent are given their broadest reasonable construction in light of the specification of the patent in which they appear. 37 C.F.R. § 42.100(b). Claim terms are given their ordinary and customary meaning as would be understood by one of ordinary skill in the art in the context of the entire disclosure. *In re Translogic Tech. Inc.*, 504 F.3d 1249, 1257 (Fed. Cir. 2007). An inventor may rebut that presumption by providing a definition of the term in the specification with reasonable clarity, deliberateness, and precision. *In re Paulsen*, 30 F.3d 1475, 1480 (Fed. Cir. 1994). In the absence of such a definition, limitations are not to be read from the specification into the claims. *In re Van Geuns*, 988 F.2d 1181, 1184 (Fed. Cir. 1993).

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